Metallic Contaminants Generation from Tubing during Start-up and Following Moisture Upsets in HCI Distribution Systems

Contamination control has alwuys been an important issue for IC manufacturing processes. Within the area of corrosive gas distribution, metallic contamination is a constant threat to process yield. This paper focuses on metallic contamination resulting from low pressure HCI gas flow *through tubing materials during system start-up and following exposure to moisture. The paper discusses the effect* **of** *HCl exposure on two tubing materials. Data relating to the type, physical state, and concentration of metallic contamination is included. Surface chemistry mechanisms are proposed in relation to the observed phenomena. The comparison of two tubing materials permits performance, cost and design implications to be considered.*

INTRODUCTION

As device size continues to shrink, the influence of contamination grows in importantance. The typical approach in minimising contamination related to gas supply, is to increase the purity specifications of gases at the point of **use.** It is generally accepted that gas punty must increase by a factor of 10 for each technology level size decrease [1]. Consequently, gas suppliers, equipment manufacturers, piping specialists, and those responsible for contamination control need to extend their knowledge of gas behaviour in distribution systems. In inert gas distribution systems, e.g. N_2 , moisture is considered by many **as** a predominant contaminant and has been analysed extensively in the past **[2].** These systems are generally well understood and computer models exist which accurately predict their behaviour **[3].**

The area of corrosive gas behaviour within a piping system is more challenging because of the additional surface chemistries and reactions that affect the piping surface structure, leading to the generation of metallic contaminants. This corrosion can lead to the premature failure of sensitive gas system components, such **as mass** flow controllers and pressure regulators, leading to costly repairs and even costlier down-time. Moisture in reactive gases enhances corrosion of piping materials. In previous **research,** BOC **and IMEC have focused on moisture** transport in HCI gas distribution systems **[4].** Relatively little is known, however, about volatile (gas phase) metallic contaminants which can be produced from corrosive gas interactions with metal surfaces.

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This paper focuses on metallic contamination resulting from HCl **gas** flow through tubing materials during system start-up and following exposure to moisture. These moisture upsets simulate the effect of moisture introduction to the system, representative of an improper cylinder change-over procedure resulting in an ingress of moisture, or inadequate purging resulting in moisture outgassing when HCl is introduced [5]. HCl was selected as the typical corrosive gas due to its widespread use in plasma etching and thermal oxidation processes.

EXPERIMENTAL

The experimental rig shown in figure 1, was designed and constructed to enable metallic contaminants to be counted and captured during dynamic process conditions, illustrative of those experienced in fab gas lines at the point of use. **Low** pressure conditions permit Joule-Thomson effects to be eliminated. **J-T** effects are normally experienced following expansion from a high pressure to a corrosion.

Figure 1. Schematic of experimental **rig**

The rig configuration permitted mixtures of purified HCI **and N, mixed with cadibrated H,O concentrations.** *tb* flow through the test material, which was maintained at a controlled temperature of **25** "C. All upstream peripheral tubing consists of EP-SS up to the point where the two streams meet. **Parts** wetted by moist HCl are made of Ni200 or PFA to minimise system contributions to the measurements. The gas exiting the test piece is scrubbed in two quartz bubblers. Data on the metallic content of the **gas** flow is obtained using TXRF (Atomika 8010) to analyse microsamples of the bubblers' solutions dried on Si wafers. The TXRF limit of detection is $\sim 10^{11}$ atoms/cm². The actual detection limit for gaseous concentrations depends on gas flow rate and time **as** well as bubbler and sample volumes, resulting in a dependency on flow time **as** shown in **Fig.** *2.*

Figure *2.* Limit of detection for metals in HCl **gas** flow as a function of **flow** time.

By installing a $0.003 \mu m$ in-line particle filter (Millipore Wafergard GT Plus, PTFE membrane in PFA housing) upstream of one of the two bubblers, differentiation between total contaminants and small contaminants, i.e. small particles $(< 0.003 \mu m)$ and/or volatiles, is possible. The filter used is of a similar specification to those installed in fabs at POU, the principal difference being that it is nonmetallic to prevent background interference.

In this paper, results are presented for the corrosion of the two predominant fab piping materials, 316L **EP-SS** and Hastelloy C-22. The tubes are 6m in length and coiled to a diameter of 10". Each tube has VCR connectors of the same material welded to each end and are cleaned **with** acetone and DIW and baked for 24 hours at 150 "C prior to HC1 exposure. The experiments are performed at a pressure slightly above 1 atm under a total flow of 0.2 SLM. **This** flow is either purified HCl (Millipore Waferpure **WPRV** 200SC, <100 ppb H₂O), simulating normal flow conditions, or 'moist' HCI, a *50/50* **mixture** of **HCI and** moist **N2 giving** IO ppm moisture in HCI. The moist HCI is admitted for periods of 1 to 3 hours to simulate moisture ingress into a distribution system.

RESULTS

The main contaminants generated during the exposures of both EP-SS and C-22, are Fe, Ni and Zn. Trace amounts of Cu and Cr were also observed but not in sufficient quantities to enable trends to be viewed. Tables 1 and *2* highlight the average contaminant concentration (volumetric) in HCl during the initial exposure of the test materials.

Upon comparing the **TXRF** data in relation to the experimental time, Figures 3 and **4,** clear trends emerge. During initial exposure the contamination levels rise over the initial 6 hour period and then decrease. Upon exposure to moist HCl for 1 hour the trend is repeated. **A** subsequent 3 hour exposure shows a further repetition of the trend. Similar trends were observed for Ni and **Zn** in both EP-SS and C-22 tubing.

Contaminants are generated **as** both large particles and small contaminants.

Figure 4. Average Fe concentration in **HCI** flowing through **C- 22** tubing, following exposure to purified and moist HCl (\pm 3 Std.) **dev)** . (a) total contamination. (b) **small** contaminants.

DISCUSSION

Contaminant Generation

For each of the tubing materials, Fe was identified **as** the predominant metallic contaminant. Quantities of Ni and **Zn** were **also** identified along with trace amounts of Cr and Cu. With the exception of Zn. each of **identified metals can be** found in C-22 and **EP-SS** tubing. Background interference was accounted for and confidence regarding the noncontribution from the Ni parts was high given the fact that

Ti was not detected **as** with previous **work** which included Ni tubings **[4][6].**

To understand the contaminant generation associated with initial exposure of the tubing material to **HCI, as** illustrated in Figures 3 and **4,** the surface chemistries have to be considered. It is thennodynamically possible for HCI to react with the **tube** surface oxides at room temperature to **form** metal chlorides. **For** example

$$
\text{Fe}_2\text{O}_3 + 6\,\text{HCl} \leftrightarrow 2\text{FeCl}_3 + 3\,\text{H}_2\text{O}
$$

Similar equations can be derived to demonstrate that metal chlorides can also be produced from reactions of the virgin metal and metal hydroxides in HCl. Upon comparing the molar volumes of the reaction products, chlorides have higher molar volumes than the oxide, e.g. Fe₂O₃ is 30.5 cm³/mol, FeCl₂ is 40.1 cm³/mol and FeCl₂.2H₂O is 69.0 cm3/mol **[7].** The volume expansion resulting from the above reactions will increase the mechanical stresses inside the surface layer causing a "flaking off" of particles. Volatiles will contaminate the gas flow **as** a result of the relatively high vapour pressure of the corresponding corrosion product. *As* HCl continues to flow, most probably a chloride layer forms on top of the oxide layer, protecting the tubing wall against further corrosion, to some extent.

Chlorides are particularly hydrophilic, forming hydrates e.g. FeCl $_2$.2H $_2$ O. When moisture upsets occur, the moisture is readily absorbed by the chlorinated surface. This absorption causes volume expansion, thereby increasing the mechanical stress within the surface layer with the same effects **as** mentioned previously.

Size Distribution

From Figure 3 and **4** it can be observed **that** Fe is present **as** both large particles and small contaminants. **A** significant fraction of the generated contaminants *are* small and pass through the filter. Upon reviewing the data for both EP-SS and C-22 tubing it is not apparent that a particular metal has a preference in forming large or small contaminants. One trend which can be seen is **as** the tubing stabilises the contaminants are more likely to be small.

Material Comparison

Evaluation of the data contained within Tables I and 2 and Figs. 3 and 4 suggests that in the case of HCI gas, Hastelloy is a slightly more resistant material generating less contaminants than EP-SS for each of the three metal contaminants observed.

CONCLUSION

The present study agrees with the findings of previous research that corrosion of **316L** EP-SS and Hastelloy C-22 tubing does occur under purified HCI flow [4][6]. The trends discussed in the previous section infer that a system can achieve a stabilised state if the purified HC1 conditions are maintained following the initial exposure. However, if conditions change and moisture enters the system, more corrosion products are generated. Moisture ingress is most likely to occur during cylinder changeover or refilling of a bulk storage system. It is therefore not only imperative that those responsible for managing such tasks have correct procedures to follow but also that the connection systems are properly designed to permit adequate purging. Residual moisture lurking in a distribution syitem as a result of poor commissioning purge procedures will also create problems. Such moisture may reside in deadlegs, e.g. tie-in **points for** future lines, but will not create problems during **normal** flow conditions **as** the main flow routes have been adequately dried. However, when the system pressure drops, the deadlegs release their contents and moisture enters the mainstream lines. It is important therefore that systems are properly designed to minimise deadlegs and to permit adequate purging of the entire system. Fortunately computer model packages have been developed to help the engineers in this task [8].

The metallic corrosion products can be generated **as** both large particles $(>0.003 \mu m)$ or small particles and/or volatiles. Even with current state-of-the-art point-of-use filters, metallic contamination will still enter the process tool. **As** device geometries continue to decrease, future work will have to focus on addressing technological requirements for the removal of these small particles and volatiles. This research shows that as a system stabilises the contaminants are likely to be small particles and/or volatiles.

The tests have shown that Hasteiloy performs slightly better than 3 16L EP-SS, however Hastelloy is a more expensive material to purchase and fabricate. Given the miles of corrosive gas piping required in a fab, running the entire system in Hastelloy would involve major additional capital expenditure. One solution would be to use Hastelloy on the parts most likely to come into contact with moisture, e.g. at cylinder manifolds.

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